A 500-MS/s 8-bit SAR ADC Generated from an Automated Layout Generation Framework in 14-nm FinFET Technology



ASP-DAC 2025 University Design Contest



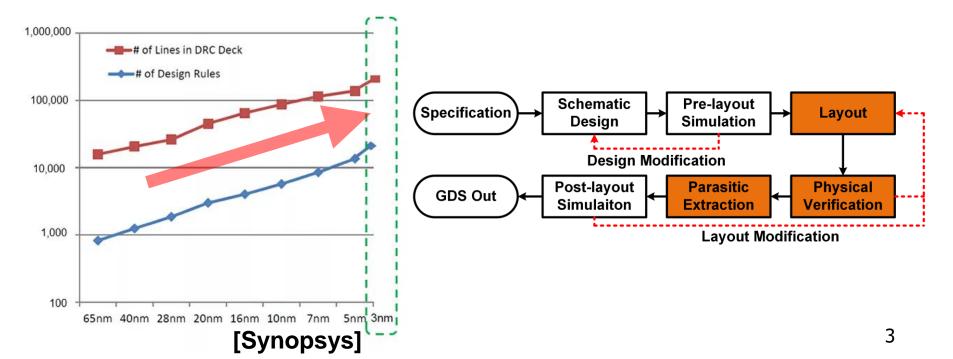
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Motivation

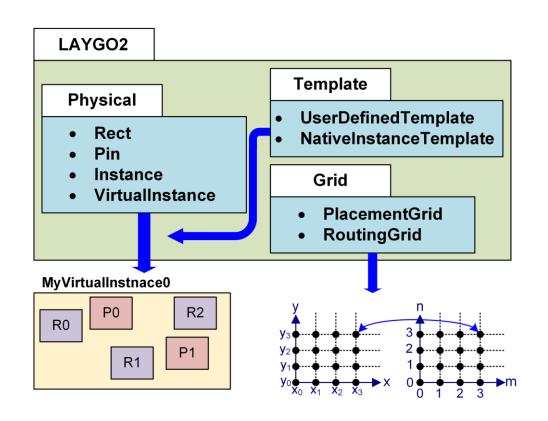
- Advanced technology nodes
 - Increased design rule & sign-off flow complexity
 - High human & time resources requirement
 - High cost in custom layout design process
 - ⇒ Need automated layout generation !

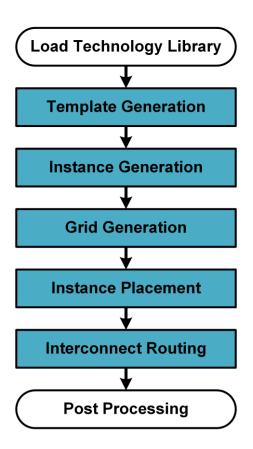


Automated Layout Generation Framework

LAYGO2

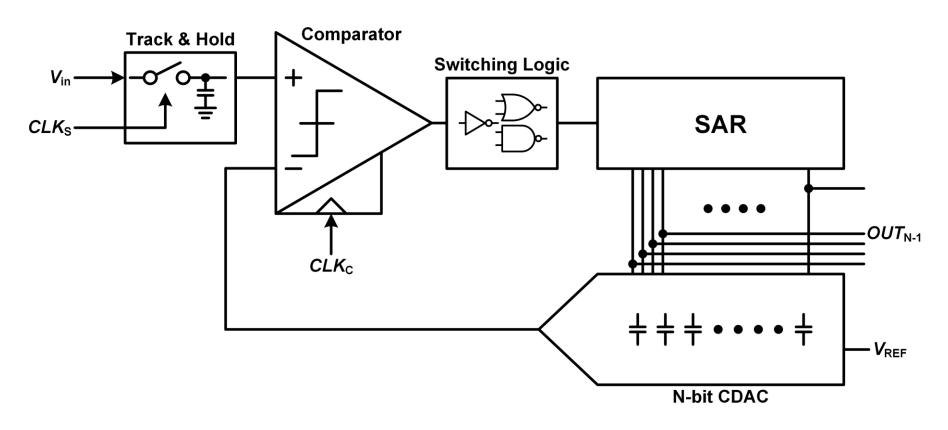
Gridded object-based layout generation framework





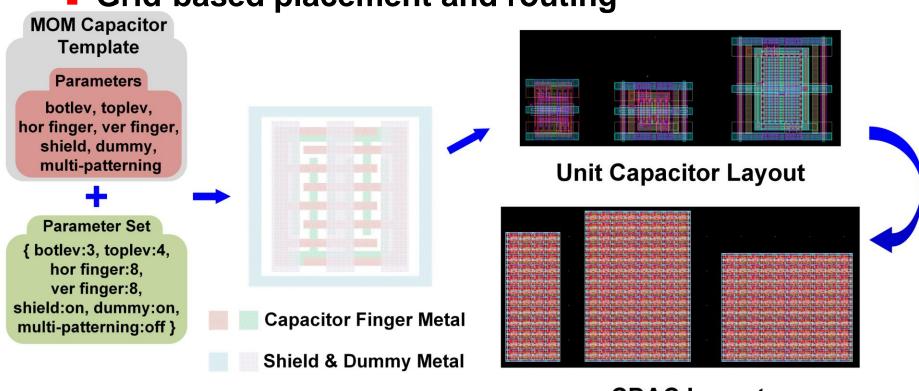
SAR ADC Building Blocks

- SAR ADC architecture
 - CDAC, comparator, track & hold, and switching logic



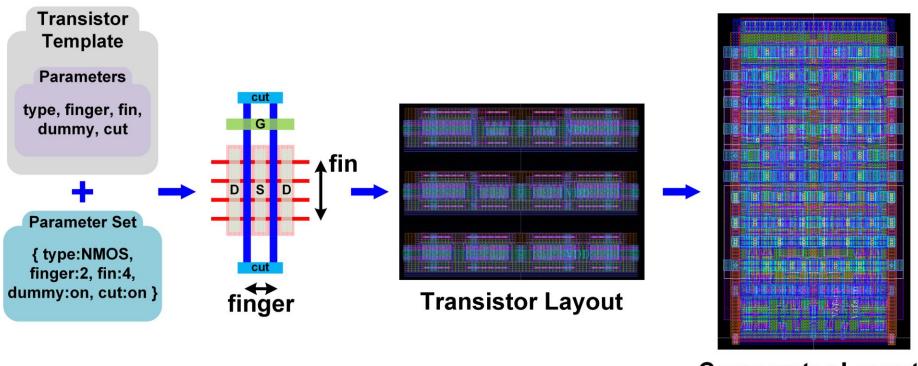
Layout Generation (1/3)

- CDAC layout
 - Software-Defined Template (UserDefinedTemplate) for MOM capacitor
 - Grid-based placement and routing



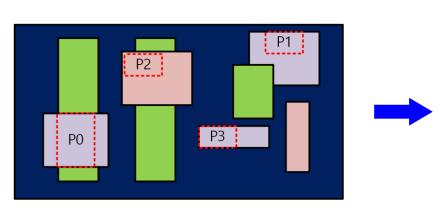
Layout Generation (2/3)

- Comparator layout
 - Software-Defined Template (UserDefinedTemplate)
 for transistors
 - Grid-based placement and routing

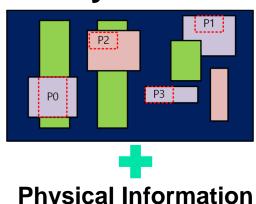


Layout Generation (3/3)

- Track & hold, switching logic layout
 - Wrapper Template (NativeInstanceTemplate) for manual structures
 - Efficient area with hand-crafted layout



Hand-crafted Layout



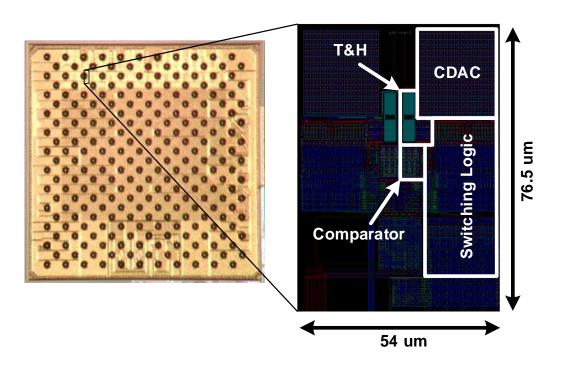
Physical Information

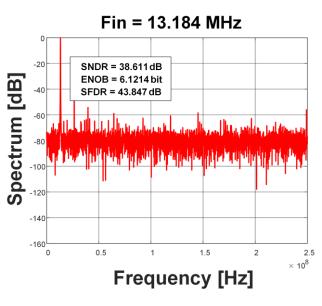
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libname='mylib'
cellname='mycell'
bbox=[[0,0],[200,100]]
pins={p0,p1,p2,p3}
```

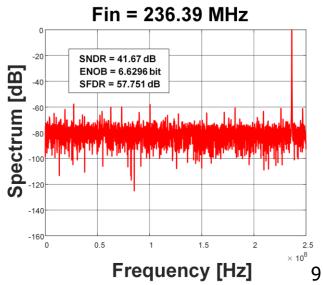
Measurement Results

Generated SAR ADC

- Fabricated in 14-nm FinFET
- Occupies 4,131 um²
- 500 MS/s with 8-bit resolution







Conclusion

- Automated layout generation in advanced technology nodes
 - Essential for addressing increasing complexity in custom designs
- SAR ADC layout generation with LAYGO2
 - Grid-based placement and routing
 - Customizable template for each building block
 - ⇒ Foundation for enhanced design efficiency

Layout mismatch mitigation & Layout productivity improvement